

Form PTO-1449

INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)

3526.2US (97-1136.02/US)

Application Number

09/585,682

Applicant K t al.

Filing Date Jun 1, 2000

Group Art Unit 2815

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
C.C.	4,529,476	07/1985	Kawamoto et al.	156	643	
C.C.	6,018,184	01/2000	Becker	257	368	
C.C.	6,066,555	05/2000	Nulty et al.	438	634	
C.C.	6,117,791	09/2000	Ko et al.	438	723	
C.C.	6,277,720 B1	08/2001	Doshi et al.	438	586	
C.C.	6,303,496 B1	10/2001	Yu	438	668	

## FOREIGN PATENT DOCUMENTS

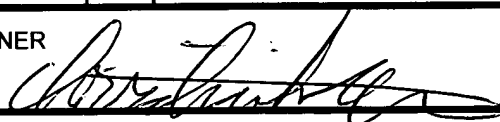
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
C.C.	61251138	08/1986	JP	—	—	X	
C.C.	0721205 A2	07/1996	EPO	—	—		
C.C.	WO 98/49719	11/1998	PCT				

## OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

C.C.		Wolf, S., et al., Silicon Processing for the VLSI Era, Vol. 1, Process Technology, Lattice Press, 1986, pp. 520-523.
C.C.		Williams, K., BSAC Etch Rates for Micromachining and IC Processing, U.C. Berkeley Microfabrication Lab., Berkeley Sensor & Actuator Center, <a href="http://www-bsac.eecs.berkeley.edu/db/etchrates.html">http://www-bsac.eecs.berkeley.edu/db/etchrates.html</a> .
C.C.		Williams, K., VLSI Etchants, Chapter 1.5, Rev. 11/97, <a href="http://microlab.berkeley.edu/labmanual/chap1/1.5.html">http://microlab.berkeley.edu/labmanual/chap1/1.5.html</a> .

EXAMINER



DATE CONSIDERED

11/4/03

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